

Draft

HELFGOTT & KARAS, P.C.
Empire State Building
60th Floor
New York, NY 10118

Telephone: (212) 643-5000
Facsimile: (212) 643-2166
or 643-0420

FACSIMILE TRANSMITTAL SHEET

DATE : January 16, 2001
TO : Examiner John S. Chu
COMPANY : U.S. Patent and Trademark Office
FAX NO. : 1-703-872-9367
SERIAL NO. : 09/036,219
FILING DATE : 03/06/1998
FROM : Aaron B. Karas

Total Number of Pages including cover ____

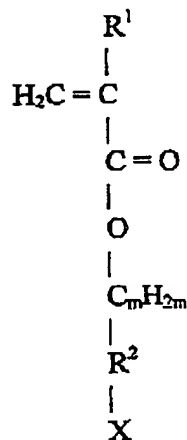
Re: Our Docket No. NEKW 14.868

As per our telephone conversation of earlier this afternoon, enclosed are two draft claims which hopefully will traverse your rejection of claim 3. Present claim 6 can then be amended to be a dependent claim, depending from new claim 22.

This communication is confidential and intended to be privileged pursuant to the attorney-client privilege and the work product doctrine. If the reader of this message is not the intended recipient, you are hereby notified that any dissemination, distribution or copying of this communication is strictly prohibited. Anyone who receives this communication in error please immediately notify us by telephone. Thank you.

CLAIMS 21 and 22

21. (New) A chemically amplified resist comprising photoacid generator contained at 0.2 parts to 25 parts by weight and polymer contained at 75 parts to 99.8 parts by weight and copolymerized between compound and at least one monomer expressed by the general formula:



wherein R^1 represents a hydrogen atom or a methyl group, R^2 represents a bridged hydrocarbon having a carbon number between 7 and 22, m equals 0 or 1 and X is selected from the group consisting of C_nH_{2n} , COOH and COOR³ where R^3 represents a hydrogen atom, a methyl



group or an acetyl group, R^8 represents a group decomposed by acid, n equals 0 or 1 and wherein said polymer has an average molecular weight ranging between 1,000 and 50,000.